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JAPANESE PATENT OFFICE

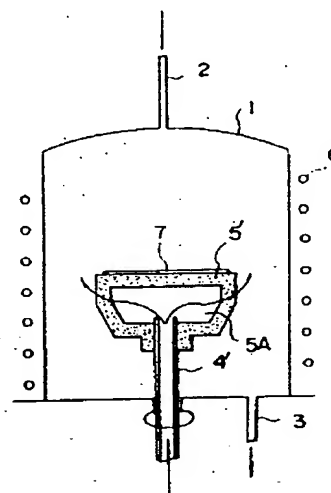
PATENT ABSTRACTS OF JAPAN

(11) Publication number: **60254610 A**(43) Date of publication of application: **16.12.85**(51) Int. Cl. **H01L 21/205**(21) Application number: **59109427**(71) Applicant: **FUJITSU LTD**(22) Date of filing: **31.05.84**(72) Inventor: **NAKAI KENYA**(54) **MANUFACTURING EQUIPMENT OF SEMICONDUCTOR**

(57) Abstract:

PURPOSE: To enable discharging impurity rapidly and easily by providing a hollow susceptor made of porous carbon.

CONSTITUTION: A manufacturing equipment of semiconductor consists of a reaction chamber 1, an air pipe 2, an exhaust pipe 3, a tube 4', a susceptor 5' and a high frequency heating coil 6. The susceptor 5' is heated by a high frequency radio wave and the heat is conducted to a substrate 7 for heating. The susceptor 5' is made of porous carbon and the inside 5A is hollow. This construction enables discharging a reaction gas rapidly and easily since the susceptor 5' is made of porous carbon even if the reaction gas is absorbed by the susceptor 5'.



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*porous hollow body
hot susceptor
woven*